



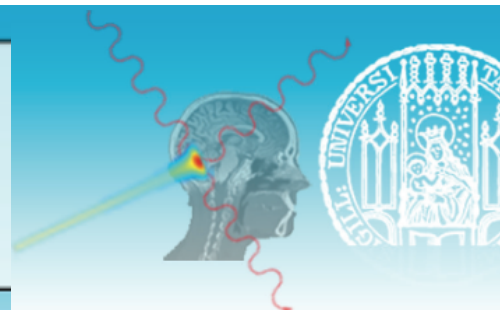
# Pixelated Low Gain Avalanche Detectors

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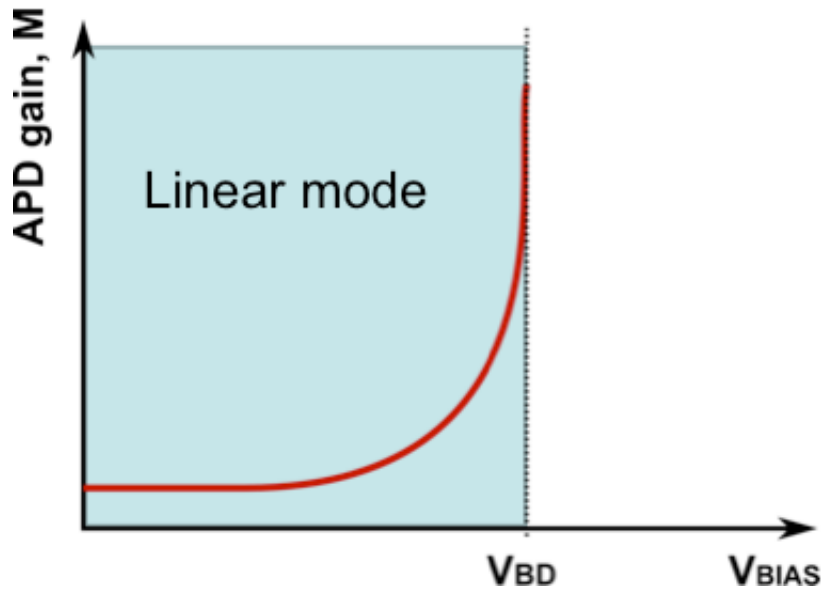
# Outline

- Introduction:
  - Avalanche PhotoDiodes (APDs)
- Low Gain Avalanche Detector (LGAD)
  - From pads to pixels
  - Proposed double-sided sensor
  - Simulated performance
- CMOS Avalanche PhotoDiodes
  - Experimental results for standard  $0.15\mu\text{m}$  CMOS
  - Gain and noise modeling
- Conclusions



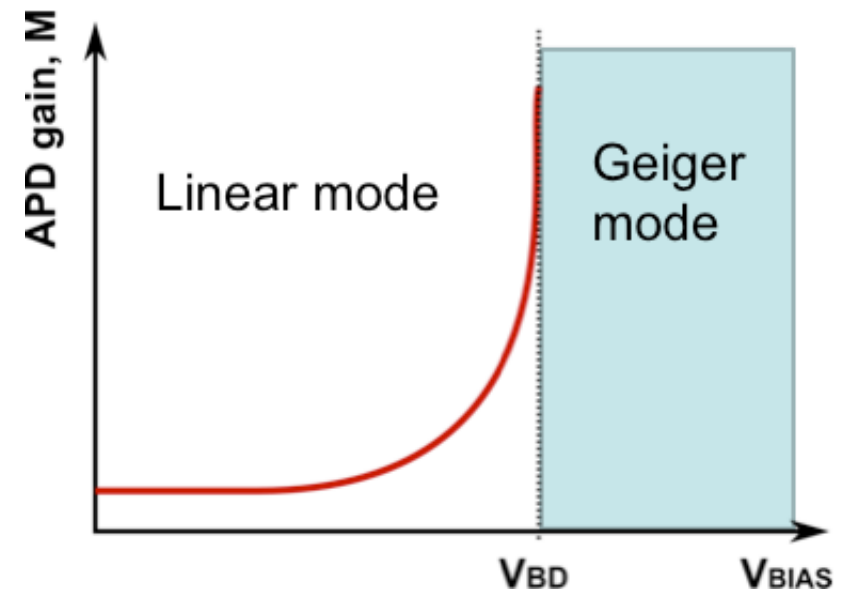
# Avalanche PhotoDiodes (APDs)

P-N junctions diodes specially made to exploit impact ionization effects



Linear mode:  $V < V_{BD}$ :

- Photo-current amplified by a factor  $M$
- Output current proportional to the optical power



Geiger mode:  $V > V_{BD}$ :

- Digital photon counter
- Output signal stream with  $N$  pulses/s
- Core of SiPMs



# Linear-Mode APDs applications

Linear-mode APDs are suitable for applications requiring **high bandwidth** and **high sensitivity**:

- Telecommunication receivers
- High speed laser scanners
- Time-resolved imaging (ToF ranging, **FLIM**)
- **X –  $\gamma$  rays, ionizing particles** for biomedical and physics applications (w and w/o scintillators)



# Linear-mode APDs Figures of Merit

- Quantum Efficiency
  - Excess noise factor
  - Gain-Bandwidth product
  - Dark current
  - Breakdown voltage
  - Temperature sensitivity
  - Breakdown voltage uniformity
  - Avalanche gain uniformity
- } Pixel Arrays



# Excess noise factor

APD noise:

$$i_n^2 = 2qI_{ph} \cdot M^2 F$$

$M$ : multiplication gain

$F$ : excess noise factor

$$F = M \cdot k + \left(2 - \frac{1}{M}\right) \cdot (1 - k)$$

Avalanche initiated by:

$\alpha$ : **electron** ionization rate

**electrons** (low  $k$ )



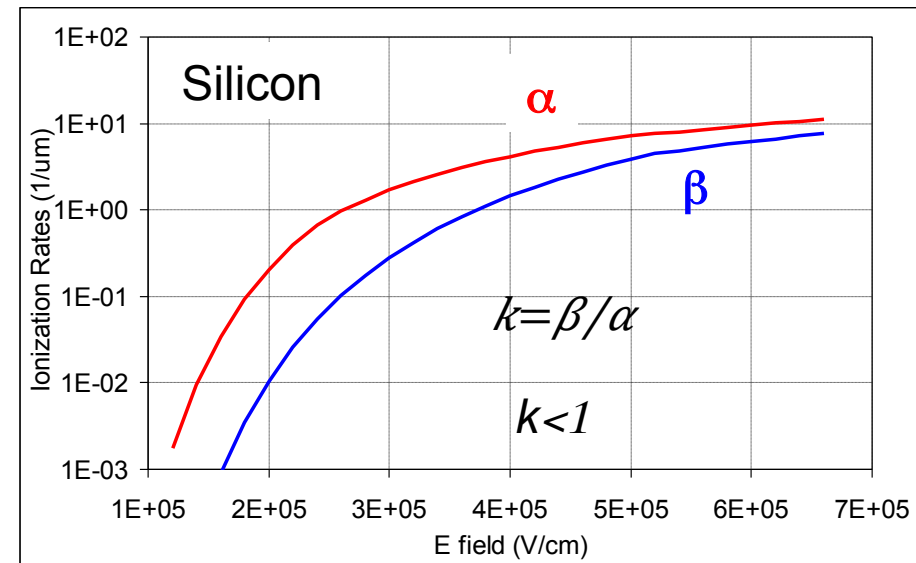
**small F**

$\beta$ : **hole** ionization rate

**holes** (high  $k$ )



**high F**



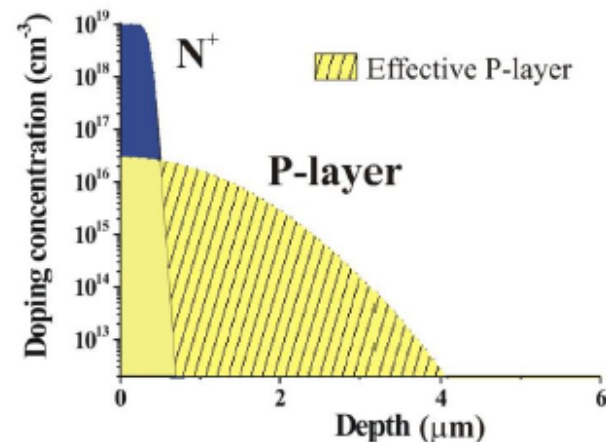
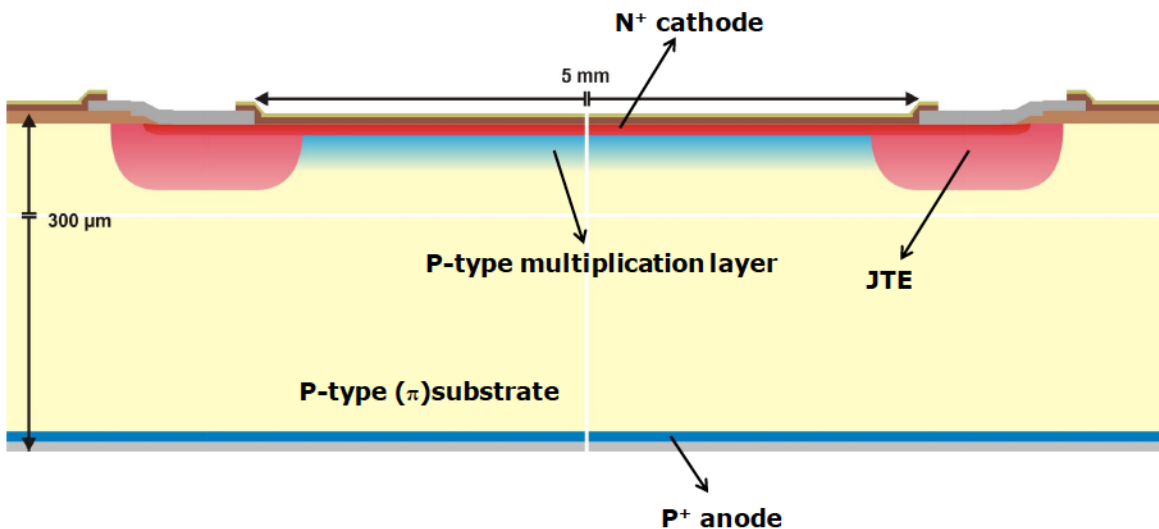
R.J. McIntyre, "Multiplication Noise in Uniform Avalanche Diodes",  
IEEE Trans. Electron Devices 13 (1966) 164



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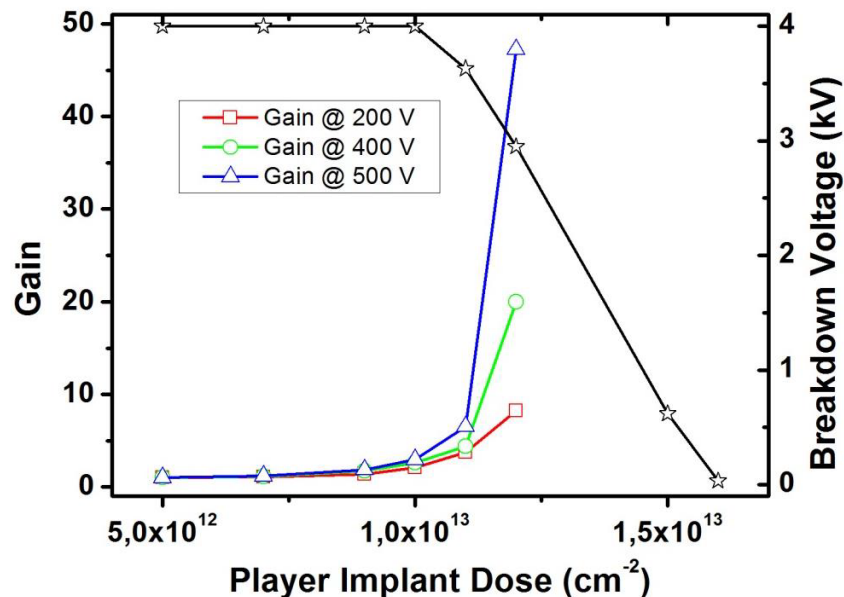
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# Low Gain Avalanche Detector (LGAD)



*G. Pellegrini, et al., HSTD9 (2013)*

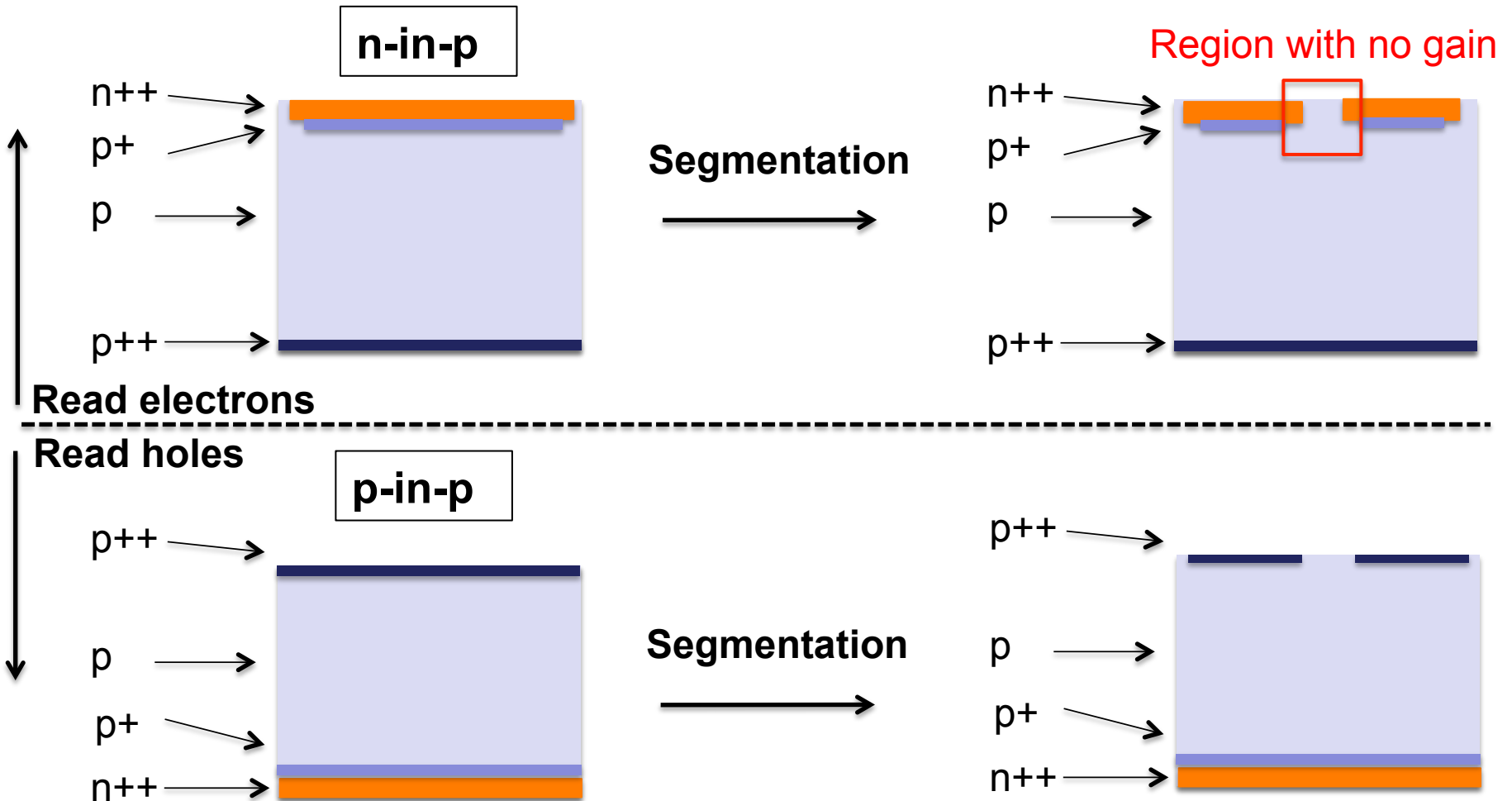
- APDs revisited for ionizing particles
- Aiming at low gain both before and after irradiation
- Gain vs breakdown voltage trade-off
- High sensitivity to the implant dose of the multiplication layer
- JTE to prevent from edge breakdown



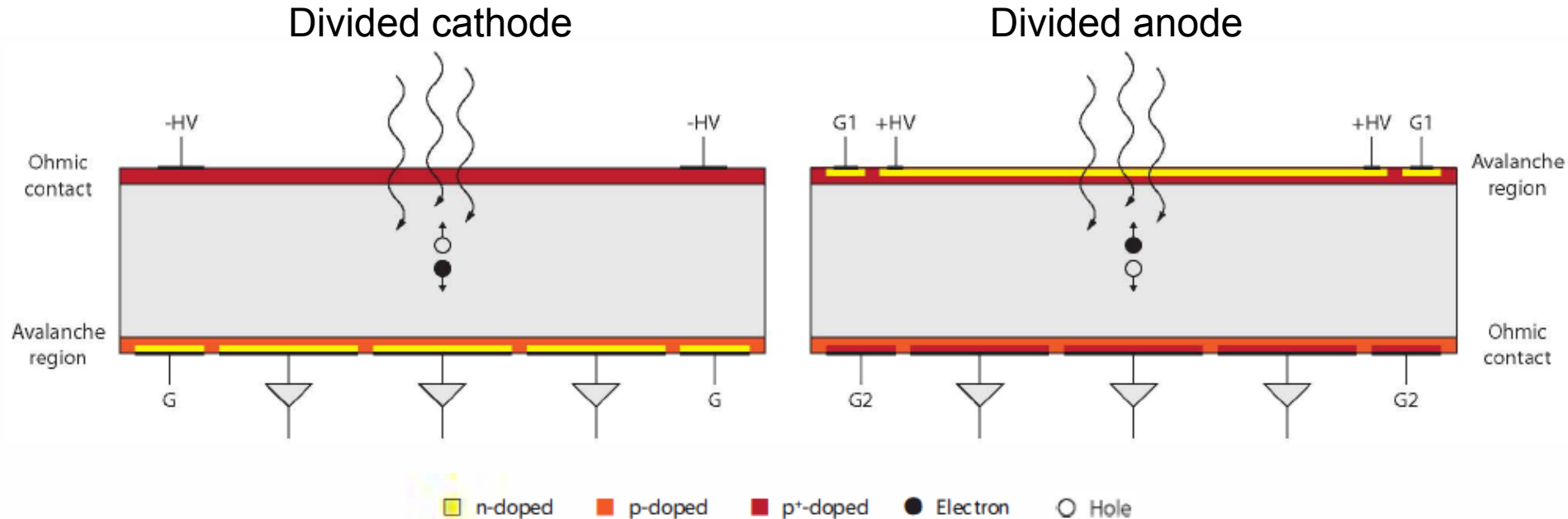


# From pads to pixels

Possible segmentation options in electron multiplying structures

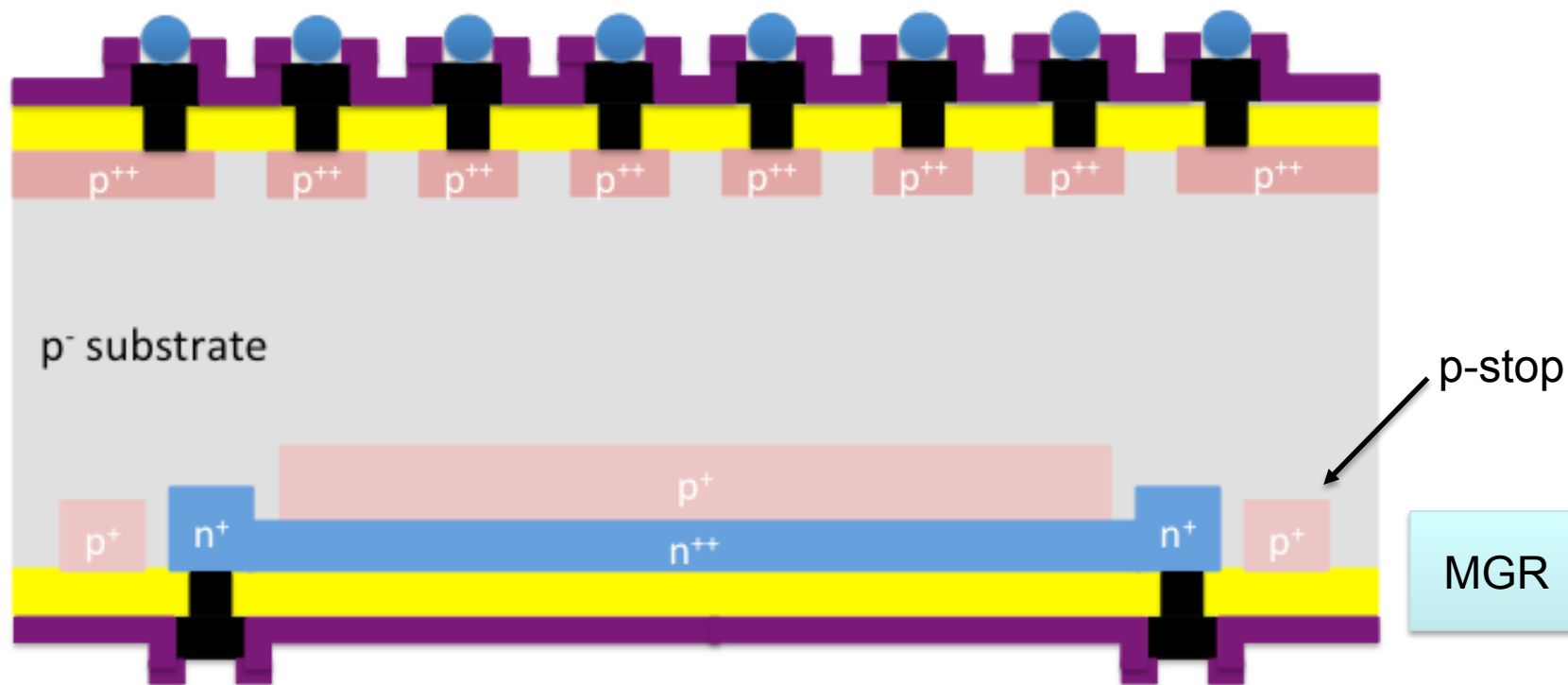


## Not a completely new problem ...



- APD arrays for fast X-ray hybrid pixel detectors
- Special technology developed by Excelitas Canada Inc.
- Thickness 120  $\mu\text{m}$  and 200  $\mu\text{m}$ , gain  $\sim 100$  @  $V_{\text{bias}} = 500\text{V}$
- Large gain non uniformity  $\pm 15\%$

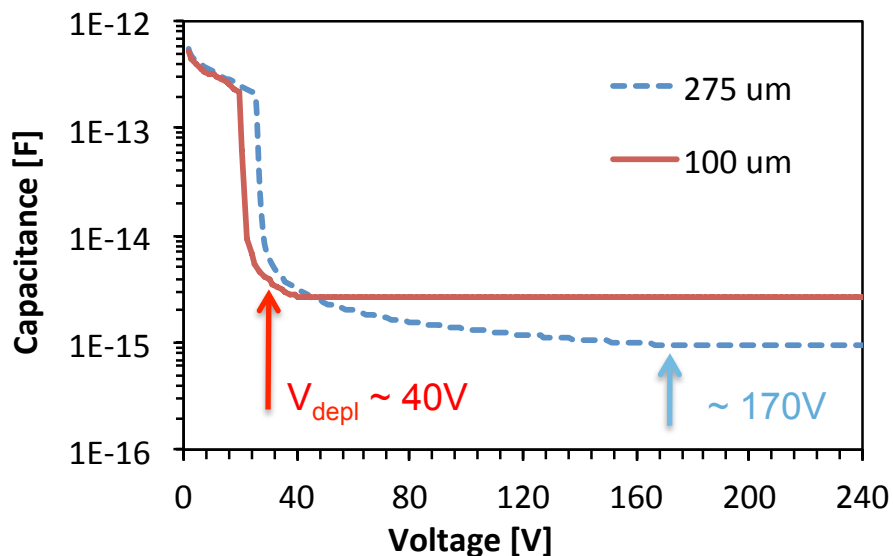
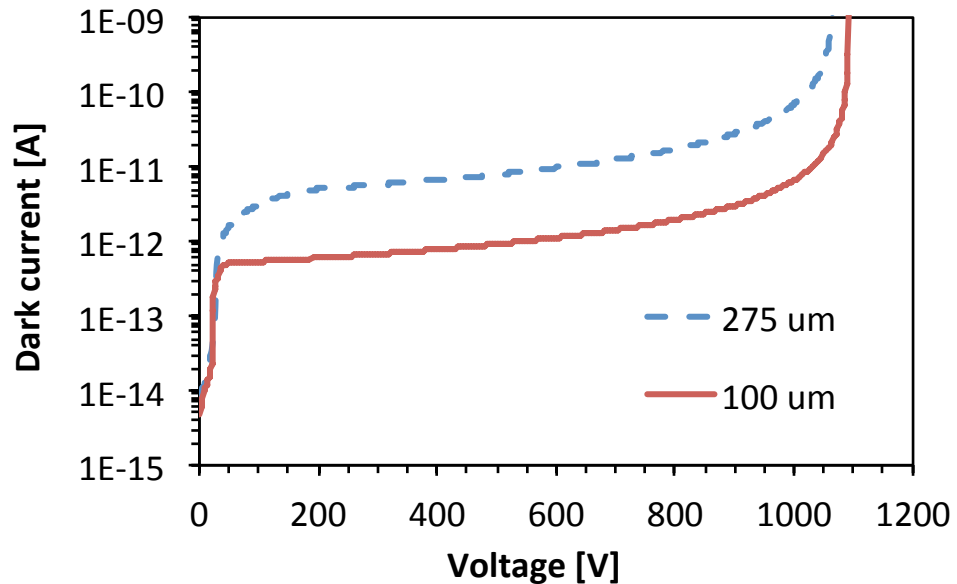
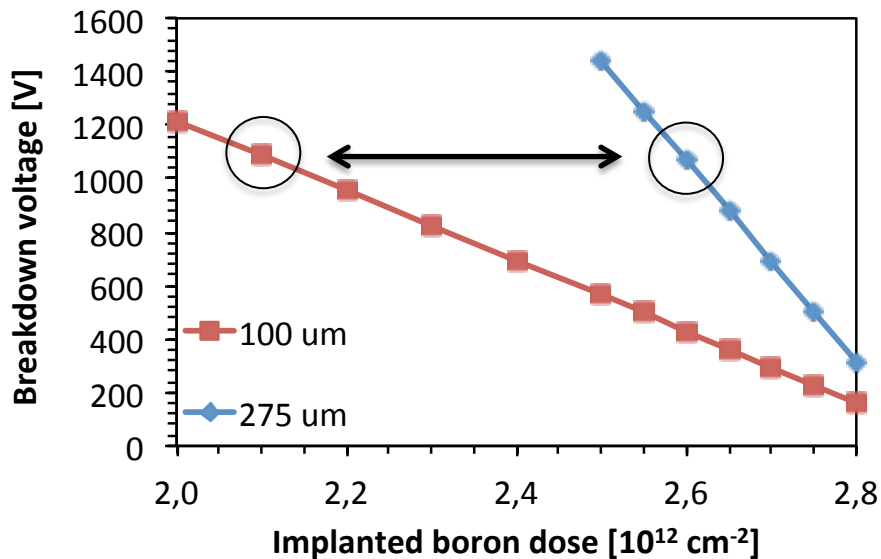
# A double-sided pixelated LGAD



- Pixel side is simple, gain side quite complex (4 doping steps)
- Plan: start from thick 6" wafers ( $275 \mu\text{m}$ ) before going thinner ( $100 \mu\text{m}$ )
- TCAD simulations to predict the performance



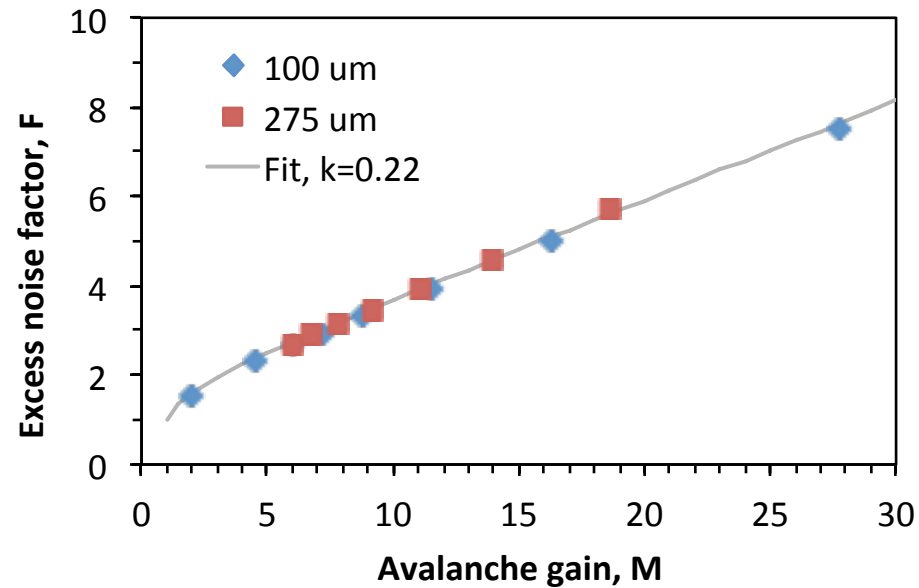
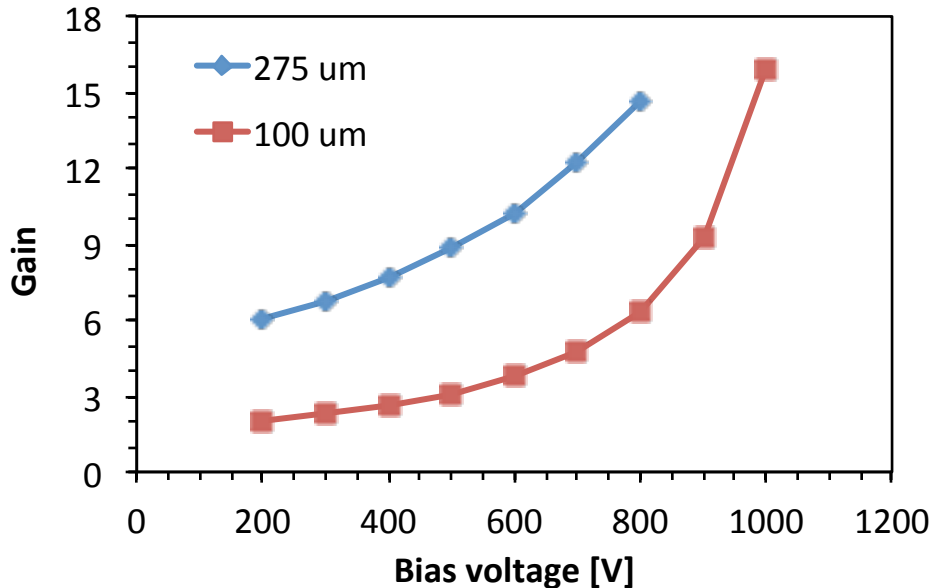
# TCAD (1): Electrical parameters



- Simulation results scaled to 50x50  $\mu\text{m}^2$  pixels
- Strong impact of the B dose on the breakdown voltage
- Comparison at similar breakdown voltage
- Two-phase depletion behavior observed in both C-V and I-V



# TCAD (2): Gain and noise



- Simulated with mip (Heavy Ion Model) in cylindrical coordinates
- Gain defined as ratio of integral charge with/without avalanche
- Similar gain at high voltage (~15) but with quite different trend

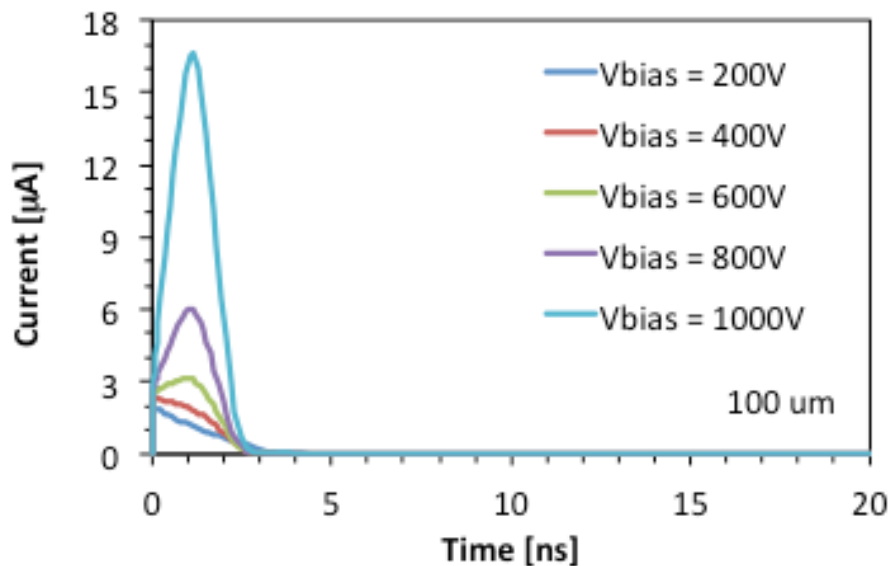
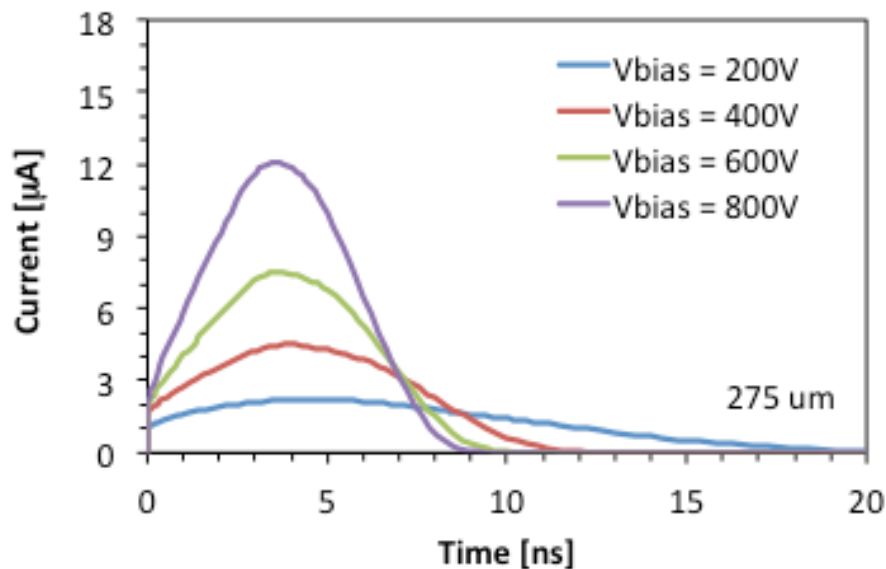
Excess noise factor can be fit with:

$$F = M \cdot k + \left(2 - \frac{1}{M}\right) \cdot (1 - k)$$

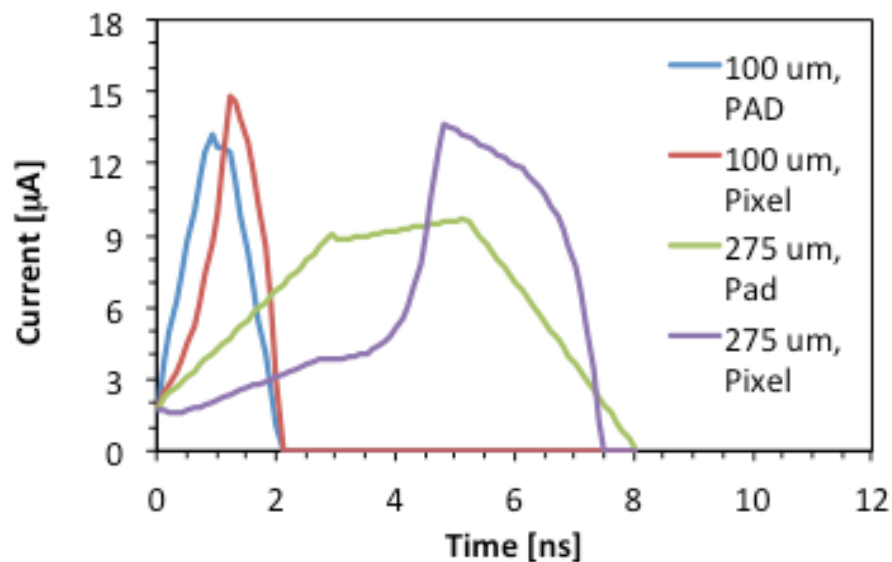
$k = \alpha_p / \alpha_n$  – ionization ratio



## TCAD (3): Signals



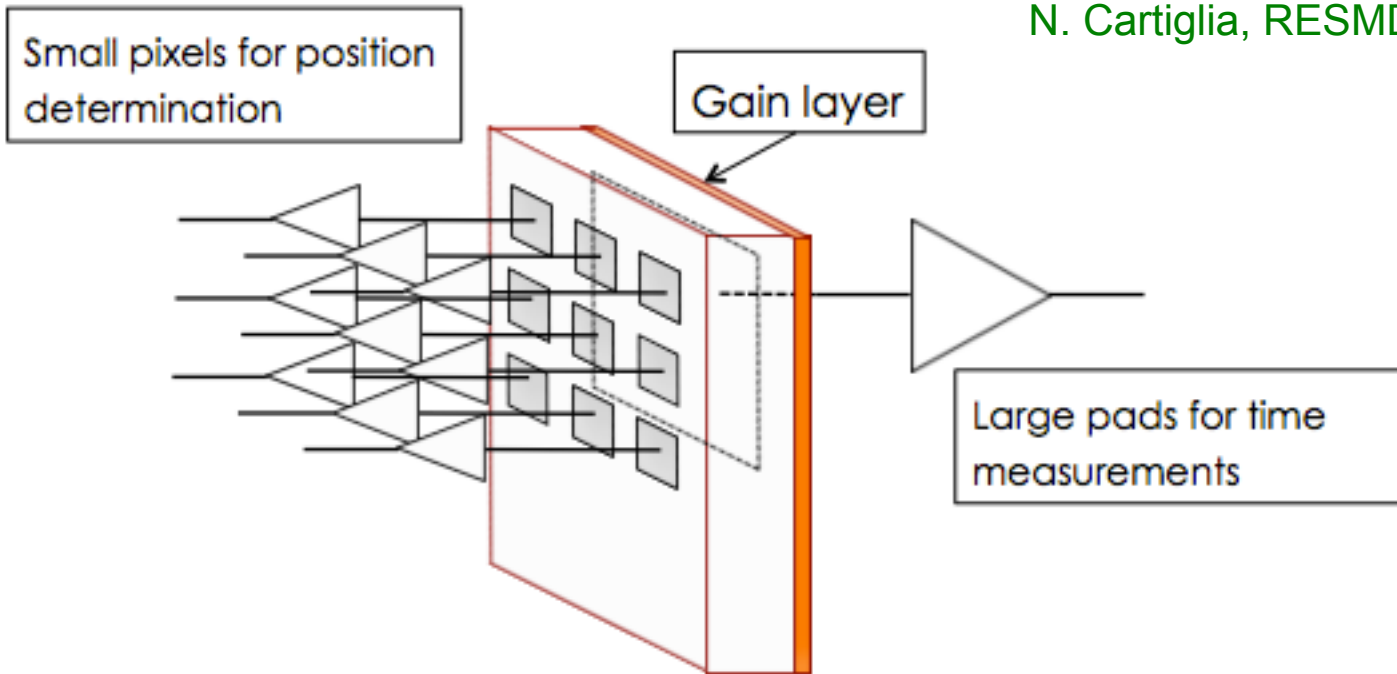
- Current pulses in response to a mip (cylindrical coordinates) at different voltages
- Pulse duration dominated by drift of multiplied holes, thus proportional to the substrate thickness
- Impact of segmentation (weighting field): significant delay for 275  $\mu\text{m}$ , much smaller for 100  $\mu\text{m}$





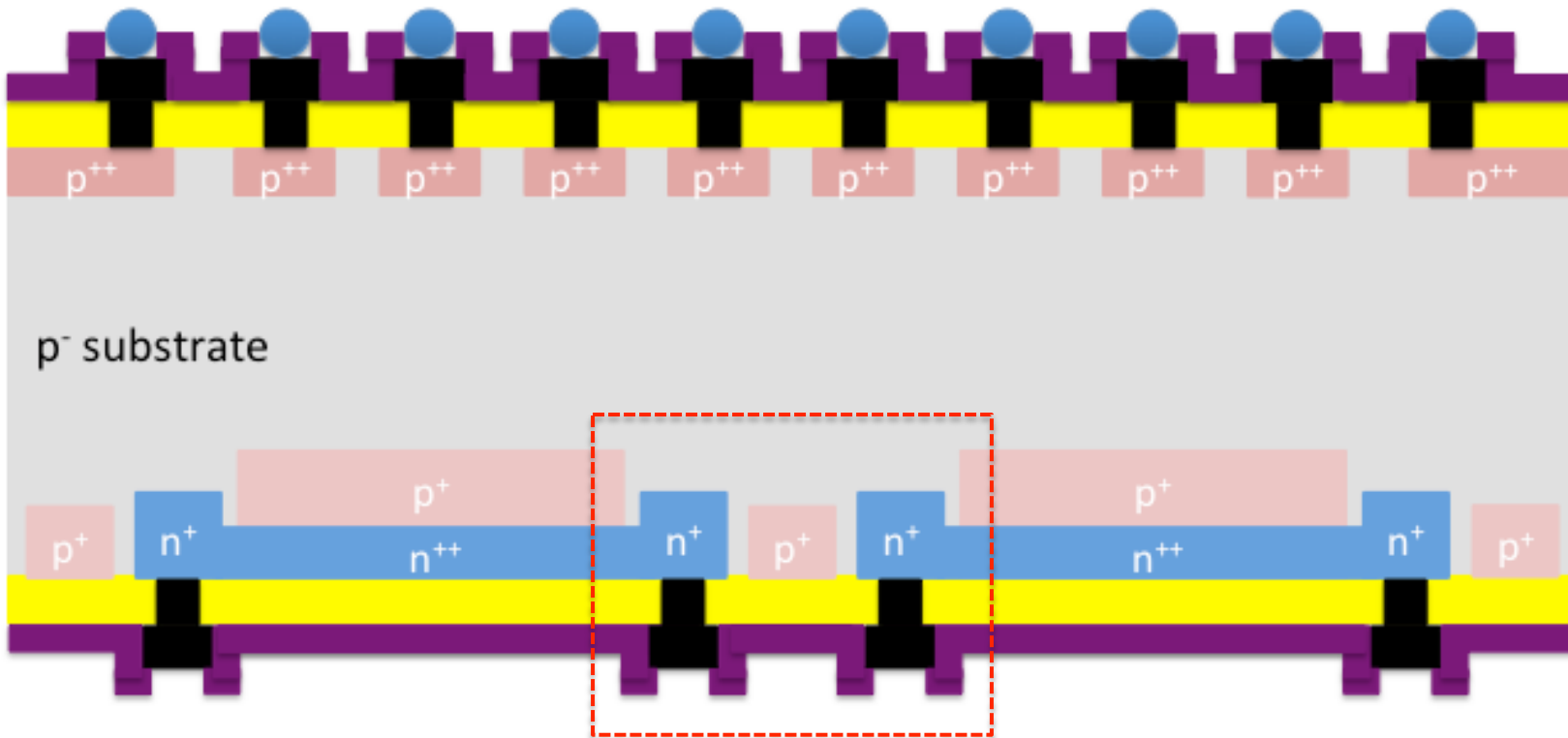
## Going one step further

N. Cartiglia, RESMDD 2014



- Fast timing circuits might be difficult to embed in small pixels
- But different functions could be divided between the two sides:
  - Position measurement from the small pixel side
  - Time measurement from the gain side → capacitance is an issue
- Segmentation of the gain side (macro – pixels,  $\sim 1\text{mm}^2$ ,  $\sim 1\text{pF}$ )

## Segmentation of the gain side



- Same technology, different layout
- Acceptable efficiency reduction from macro-pixel edges ( $\sim 5\%$ )
- It can work safely up to  $>1200V$  before breakdown





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# APD integration in CMOS

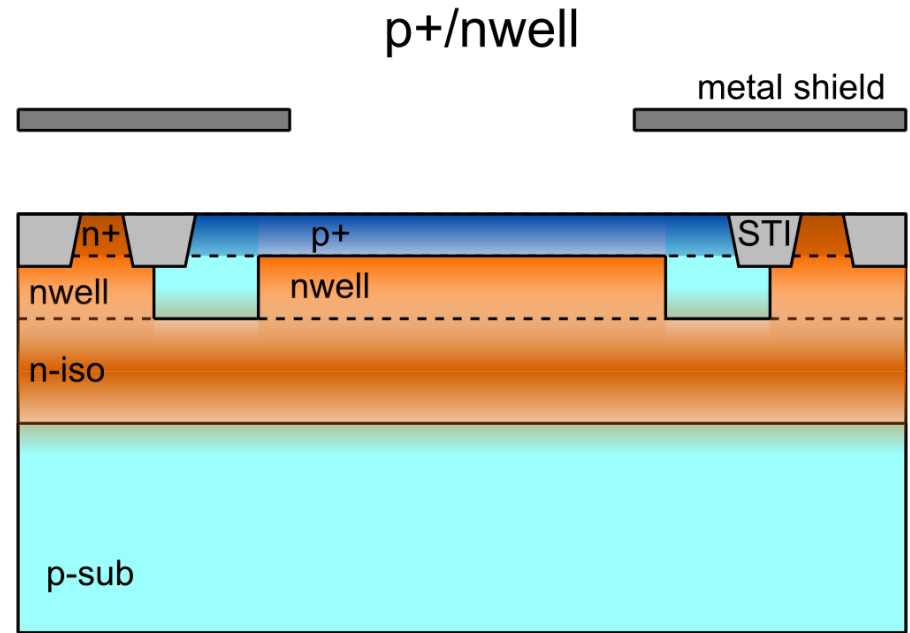
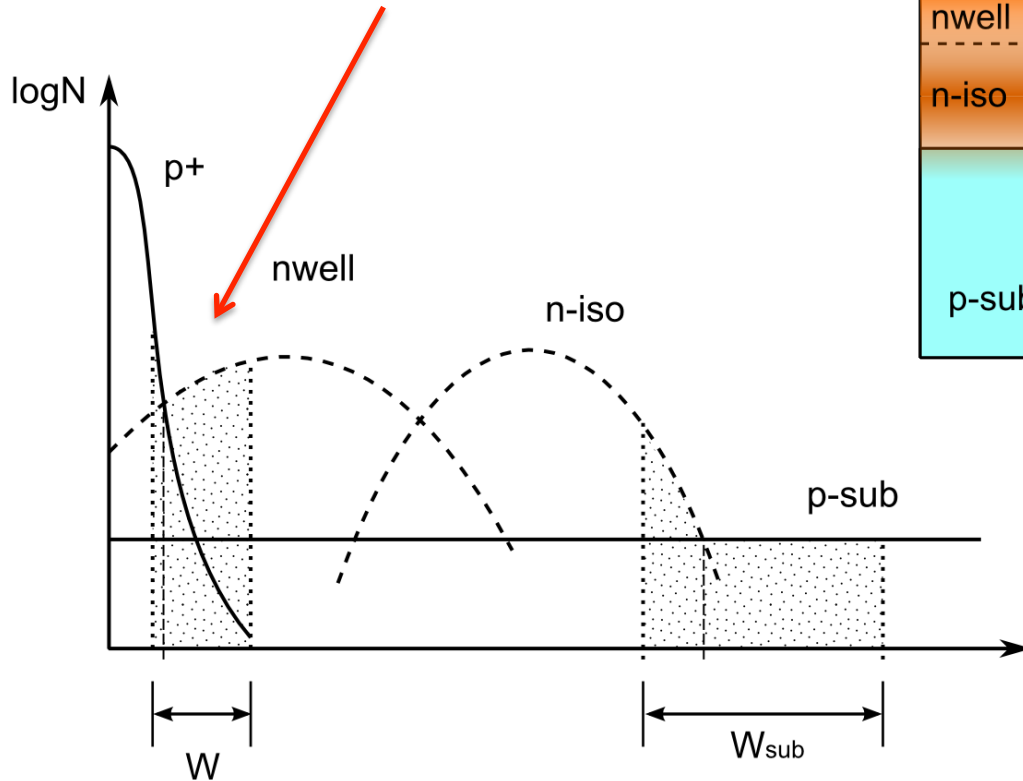
- Significant results in the past ten years
- Mainly driven by telecom receivers, but increasing interest also for imaging
- Advantages:
  - Integrated electronics: low parasitics, low costs
  - Array fabrication possible
- Challenges:
  - Guard ring fabrication
  - Doping profiles not optimized for low noise and high quantum efficiency



# p+/nwell APD in 0.15μm CMOS

L. Pancheri et al., Proc. SPIE 8982 (2014)

APD active region can be approximated with an **abrupt junction**



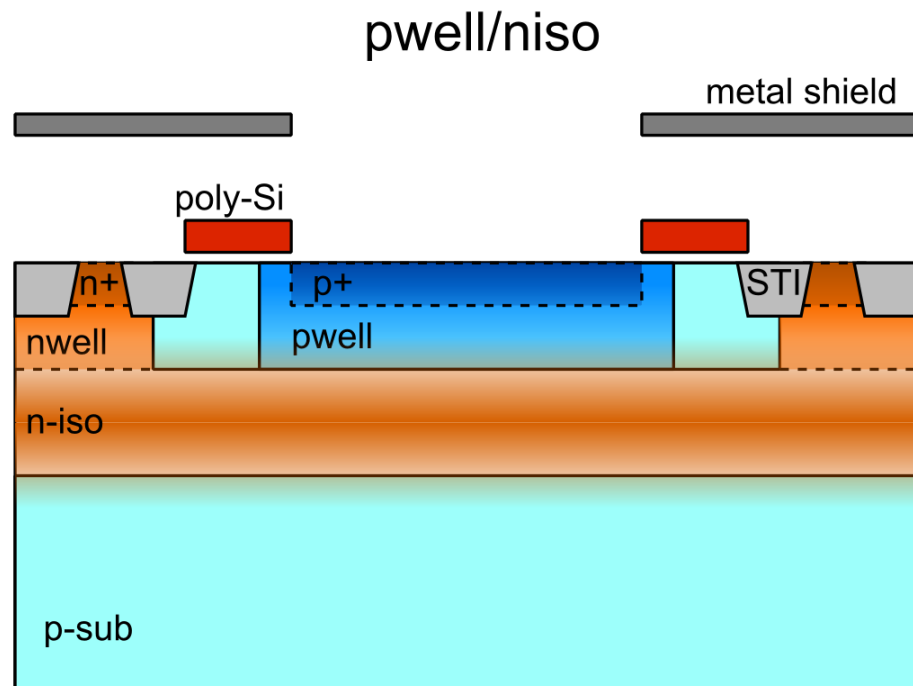
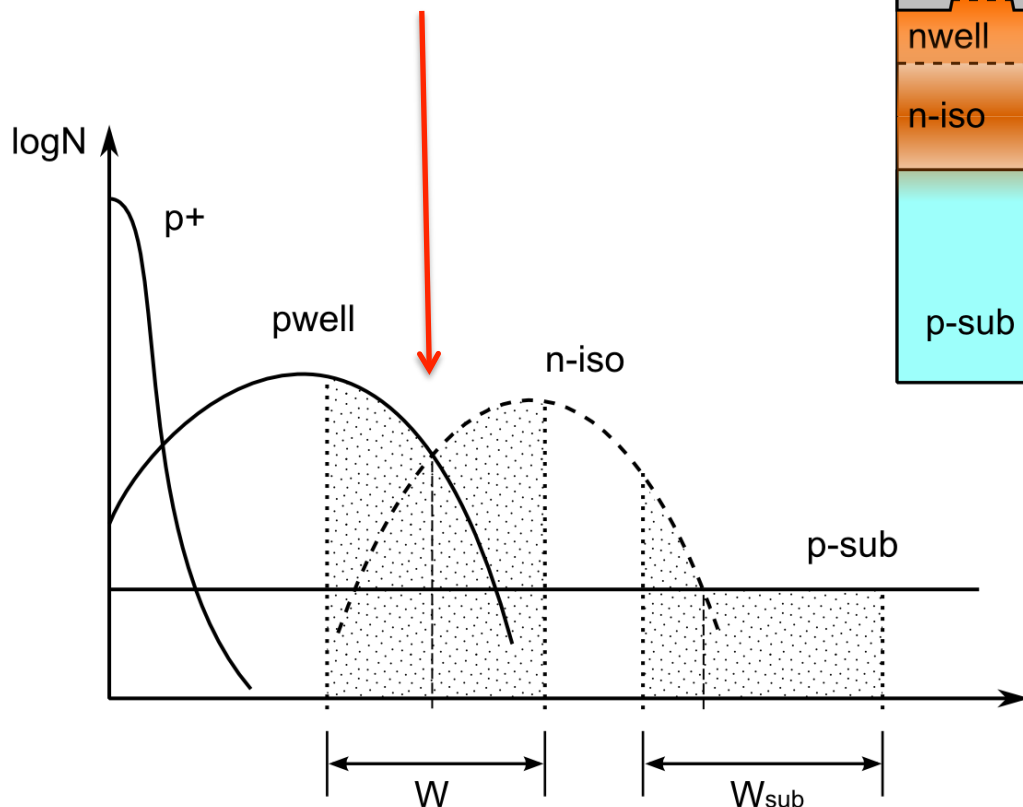
- Shallow junction  $\sim 0.2\mu\text{m}$
- p-sub low-doped guard ring
- Active region: p+/nwell junction



# pwell/n-iso APD in 0.15 $\mu\text{m}$ CMOS

L. Pancheri et al., IEEE EDL 35 (2014) 566

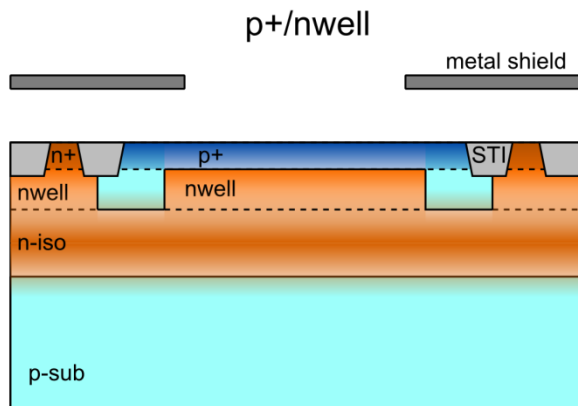
APD active region can be approximated with a **linearly graded junction**



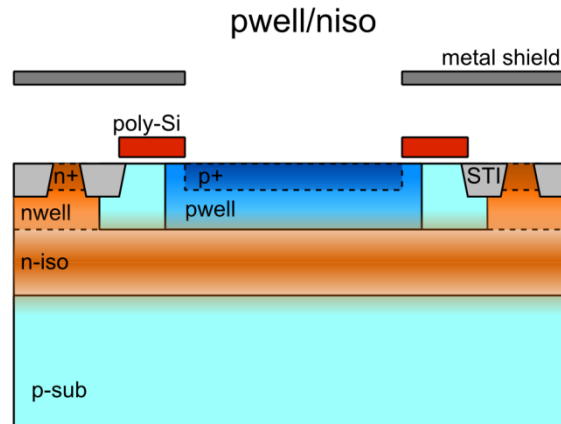
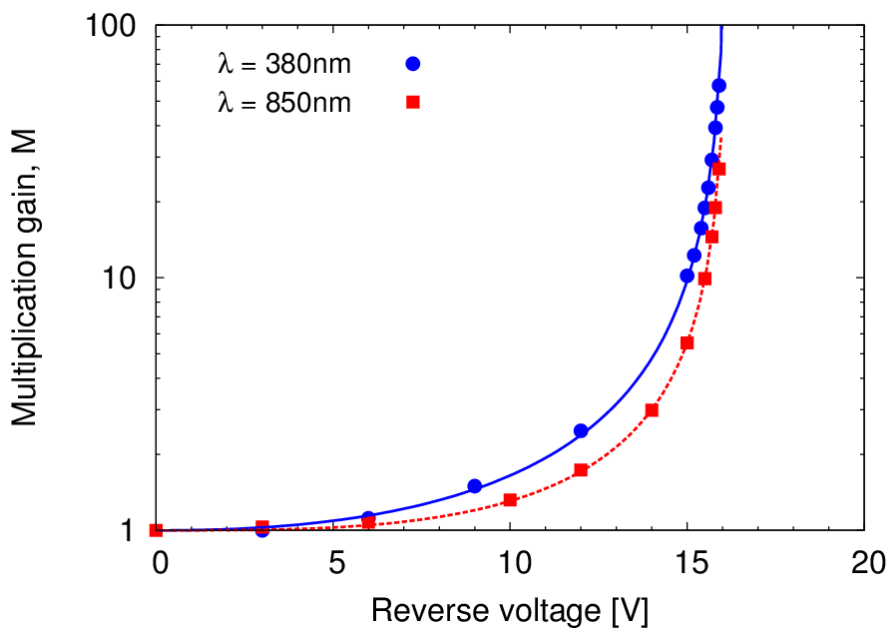
- Deep junction > 1 $\mu\text{m}$
- p-sub low-doped guard ring
- Active region: pwell/n-iso junction



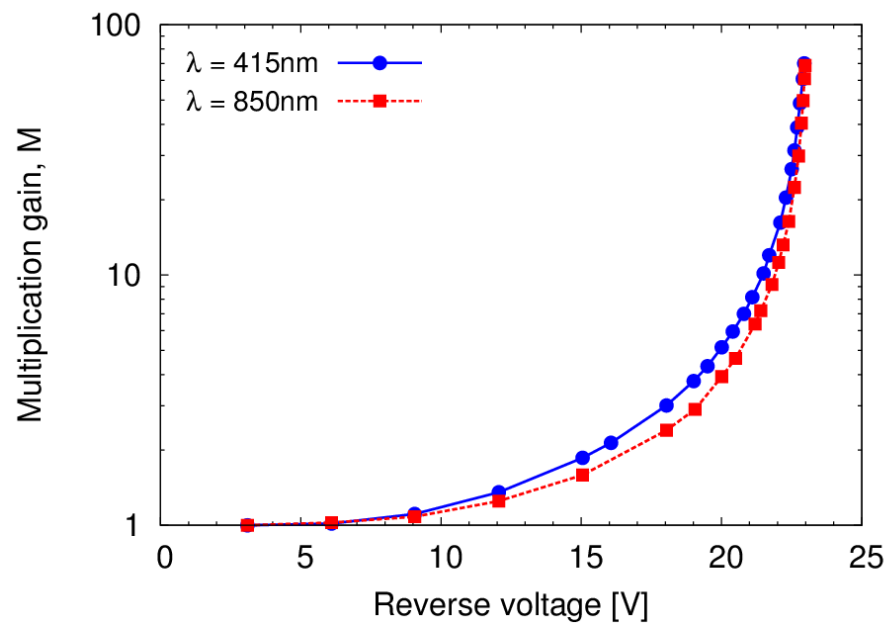
# Gain vs Voltage



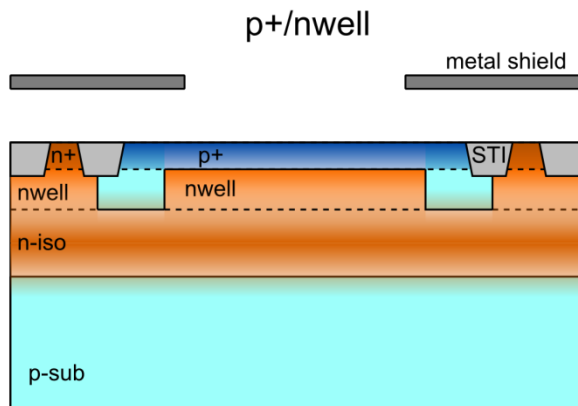
$V_B = 16.1\text{V}$ ,  $\sigma = 90\text{mV}$



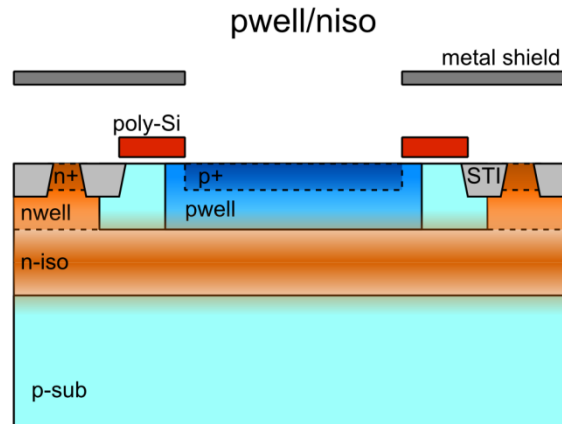
$V_B = 23.1\text{V}$ ,  $\sigma = 260\text{mV}$



# Quantum Efficiency

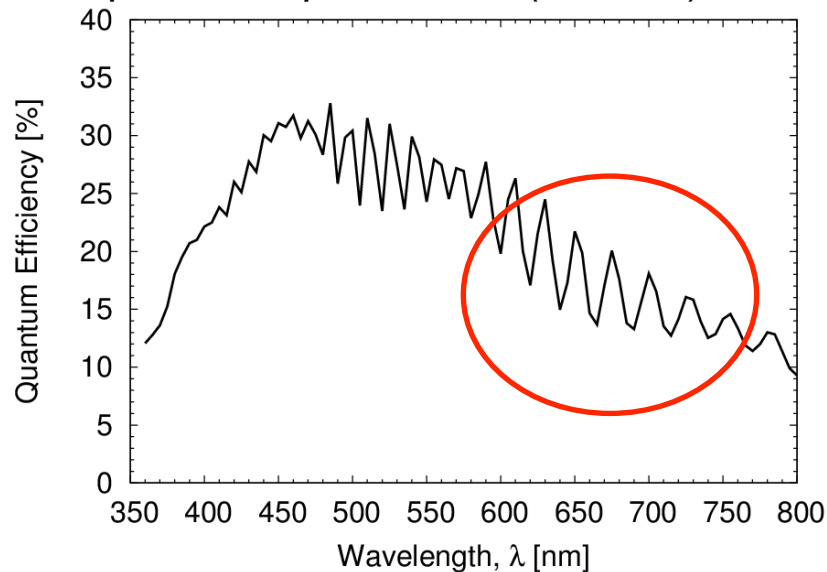
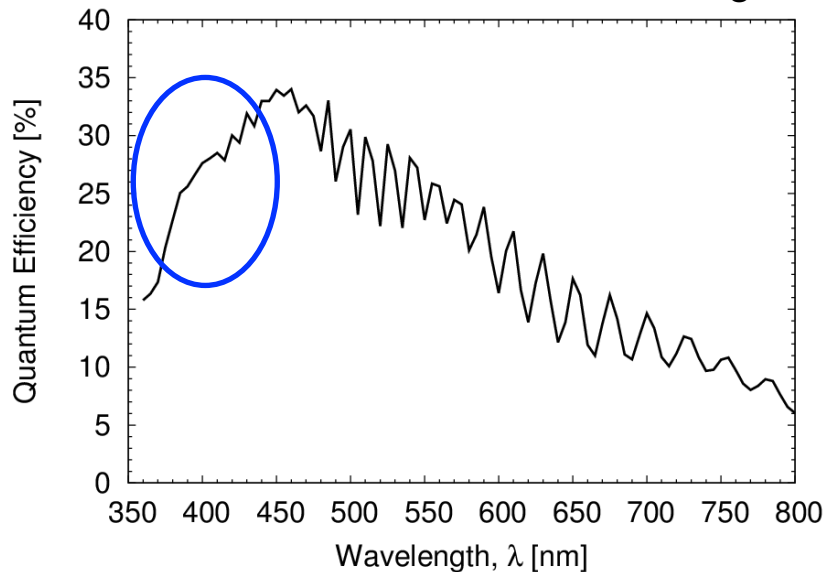


Better in the UV and blue



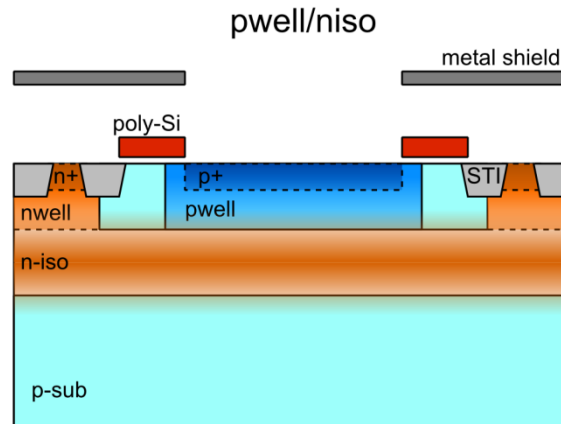
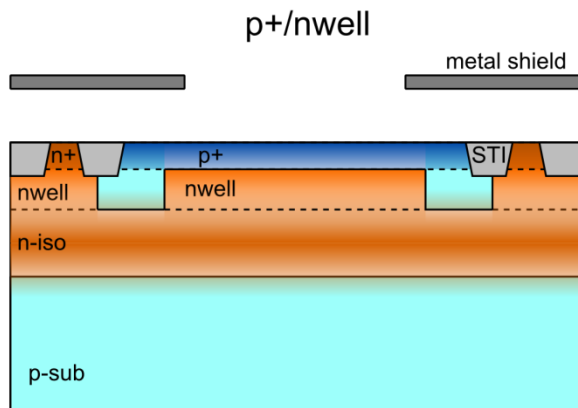
Better in the NIR

In both cases interference fringes due to non optimized optical stack (no ARC)

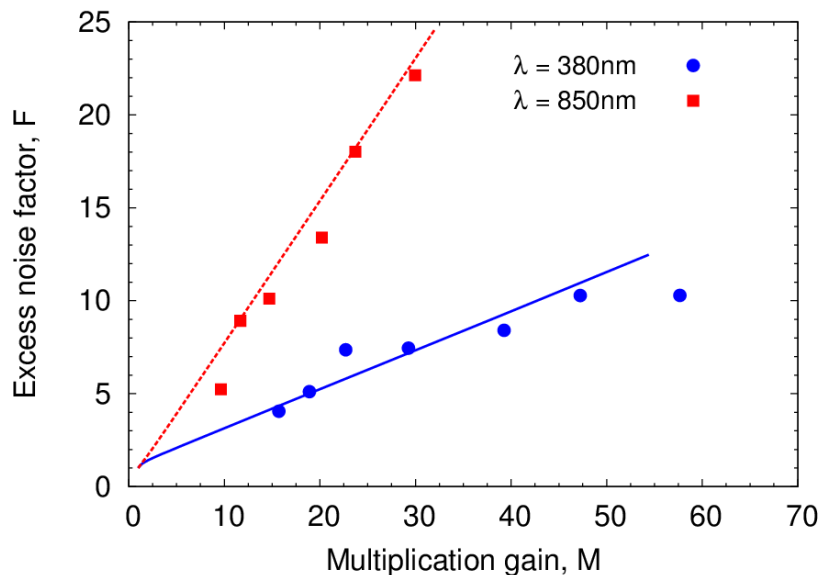




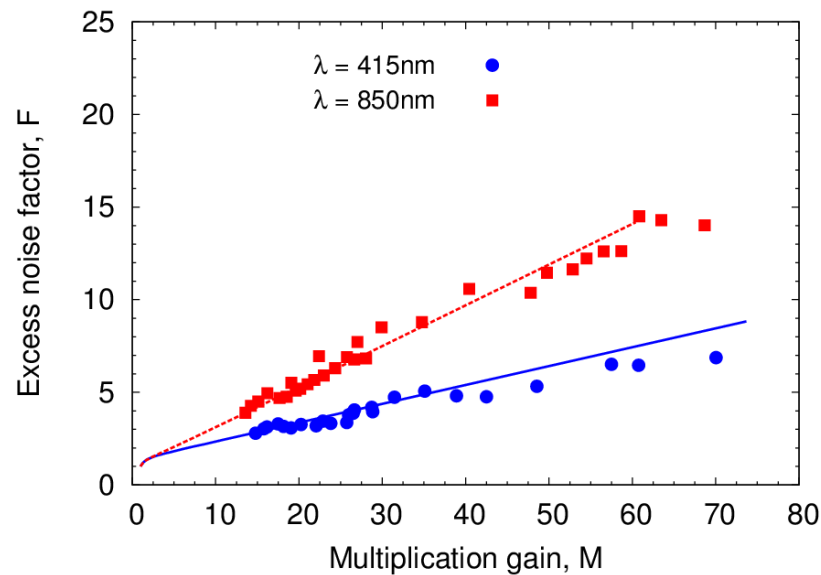
# Excess Noise Factor



- UV light: electron-initiated avalanche
- NIR light: mixed – majority of hole injection

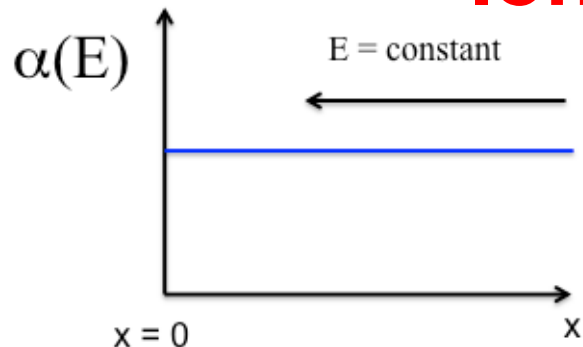


- UV light: electron-initiated avalanche
- NIR light: mixed – majority of electron injection





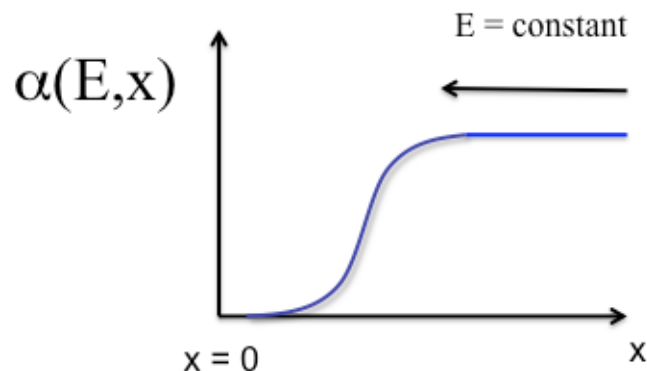
# Ionization Rate Models



## 1) Local model:

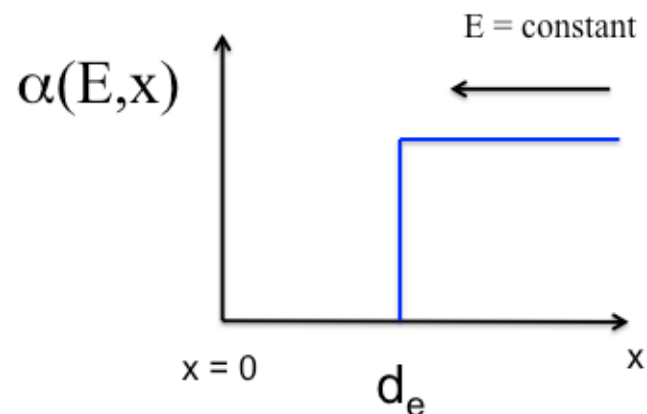
$\alpha$  depends only on the electric field  $E$

Local model: McIntyre, IEEE TED, 1966  
Ion. rates: Okuto and Crowell, SSE, 1975



## 2) Non-local model:

- The electron needs to acquire energy from  $E$  before being able to cause impact ionization
- $\alpha$  depends on electric field  $E$  and position  $x$



## 3) Simplified non-local model:

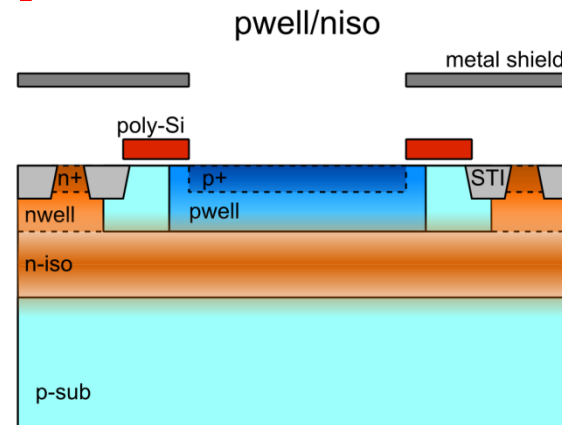
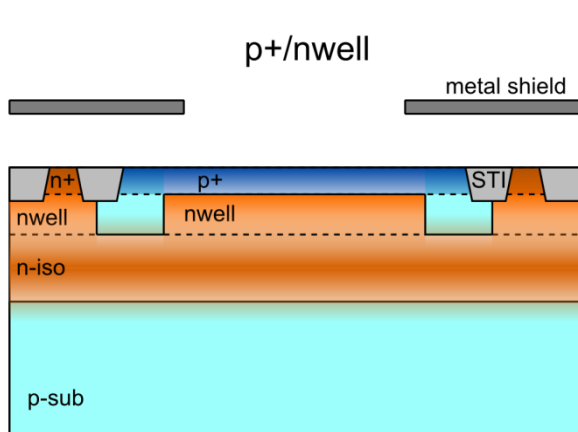
- Dead-space  $d_e$  defines a sharp transition
- $d_e$  proportional to ionization threshold energy

Non-local (dead-space) model: Hayat et al., IEEE JQE, 1992  
Ion. rates (nonlocal): Okuto and Crowell, Phys. Rev. B, 1974

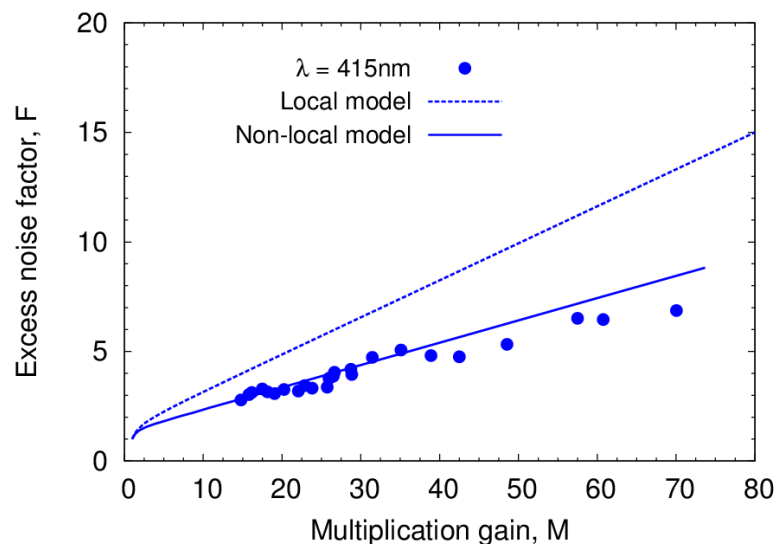
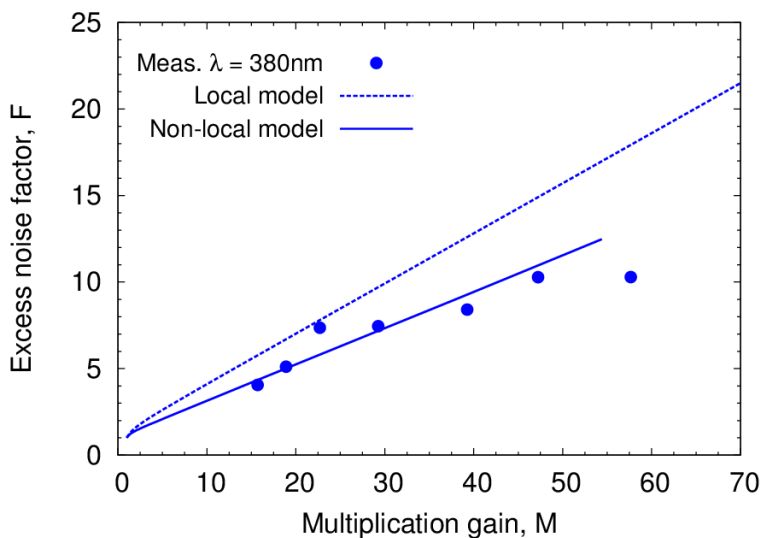




# F vs M: model comparison

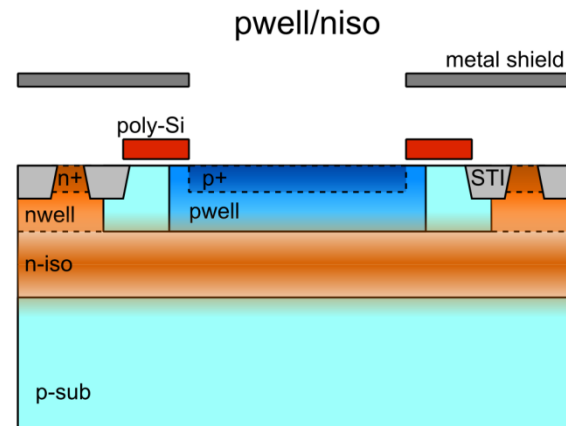
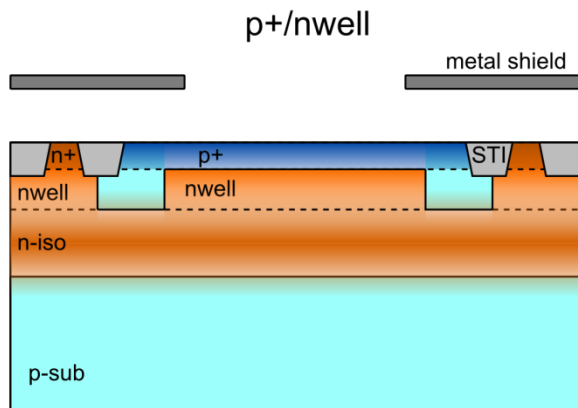


- Local model not suitable due to high electric field and narrow space-charge regions
- Very good agreement with non-local models for electron-initiated avalanche

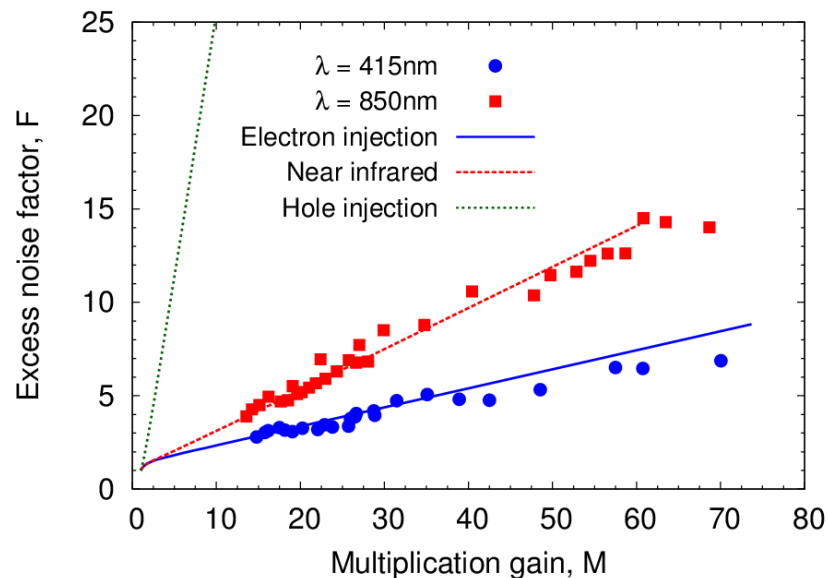
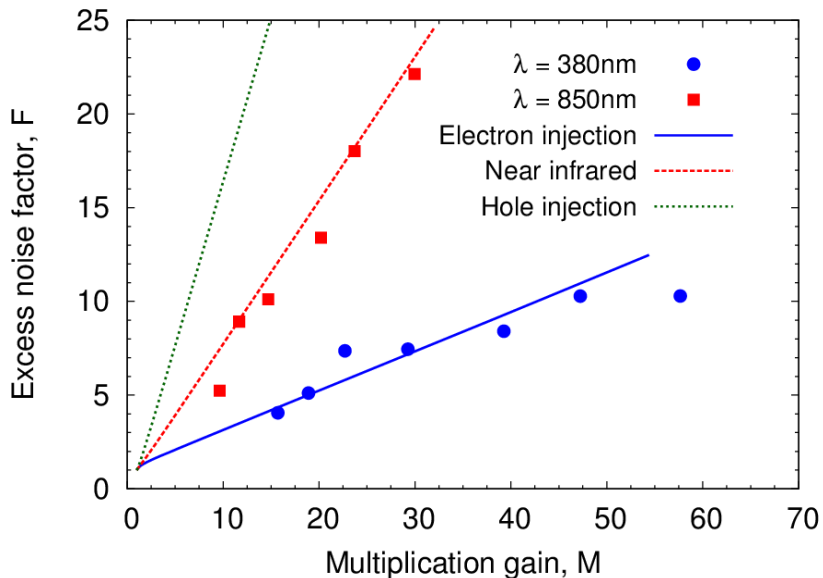




# F vs M: non-local model



- Also non-local model with hole-initiated avalanche overestimates F
- Good agreement with NIR approximation (mixed injection) with  $X_j$  as a fitting parameter





## Conclusions

- 1) Design options for pixelated LGADs were reported
  - TCAD simulations have been used to predict the sensor performance with encouraging results
- 2) Low-noise APDs can be integrated in CMOS processes
  - Good uniformity → Arrays are feasible
  - Non-local ionization models can yield an accurate excess noise predictions

## Acknowledgement

This work has been supported in part by INFN CSN5, project UFSD, and by the Autonomous Province of Trento and INFN under the framework agreement “MEMS3”